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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/522,036	01/19/2005	Kenji Maruyama	SHIGA7.004APC	1510	
20995 7590 03/06/2007 KNOBBE MARTENS OLSON & BEAR LLP					
2040 MAIN ST	REET	LEE, SIN J			
FOURTEENTH FLOOR IRVINE. CA 92614			ART UNIT	PAPER NUMBER	
,			1752		
	VII. 1944.				
SHORTENED STATUTORY	Y PERIOD OF RESPONSE	NOTIFICATION DATE	DELIVERY MODE		
3 MON	NTHS	03/06/2007	ELECTRONIC		

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

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jcartee@kmob.com eOAPilot@kmob.com

		Application No.	Applicant(s)			
		10/522,036	MARUYAMA ET AL.			
	Office Action Summary	Examiner	Art Unit			
		Sin J. Lee	1752			
	The MAILING DATE of this communication ap	pears on the cover sheet with the c	orrespondence addre	:ss		
Period fo	• •	VIO OFT TO EVOIDE AMOUTILE	(C) OD TUUDTY (20) I	DAVC		
WHIC - Exter after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLICHEVER IS LONGER, FROM THE MAILING DISTRICT IN THE MAILING DISTRICT	ATE OF THIS COMMUNICATION 136(a). In no event, however, may a reply be tir will apply and will expire SIX (6) MONTHS from the, cause the application to become ABANDONE	N. nely filed the mailing date of this comm ED (35 U.S.C. § 133).			
Status						
1)⊠	Responsive to communication(s) filed on 2/8/0	07. 2/22/07.				
, —		s action is non-final.				
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
	closed in accordance with the practice under	Ex parte Quayle, 1935 C.D. 11, 4	53 O.G. 213.	•		
Dispositi	on of Claims					
	Claim(s) <u>1,4-10,13-18,21,22,30,31,39 and 40</u>	is/are pending in the application.				
•	4a) Of the above claim(s) is/are withdrawn from consideration.					
	Claim(s) is/are allowed.					
· _	Claim(s) <u>1,4-10,13-18,21,22,30,31,39 and 40</u>	is/are rejected.				
7)	Claim(s) is/are objected to.					
8)□	Claim(s) are subject to restriction and/o	or election requirement.				
Applicati	on Papers					
	The specification is objected to by the Examine	or .				
. —	The drawing(s) filed on is/are: a)☐ acc		Examiner.			
٠٠,٥	Applicant may not request that any objection to the	' ' '				
•	Replacement drawing sheet(s) including the correct			1.121(d).		
11)	The oath or declaration is objected to by the E	xaminer. Note the attached Office	Action or form PTO-	152.		
Priority ι	ınder 35 U.S.C. § 119					
12)🖂	Acknowledgment is made of a claim for foreigr	n priority under 35 U.S.C. § 119(a	ı)-(d) or (f).			
	All b) ☐ Some * c) ☐ None of:		, , , , , ,			
	1. Certified copies of the priority documen	ts have been received.				
	2. Certified copies of the priority documents have been received in Application No					
	3. Copies of the certified copies of the price	ority documents have been receive	ed in this National Sta	age		
	application from the International Burea	u (PCT Rule 17.2(a)).				
* \$	See the attached detailed Office action for a list	t of the certified copies not receive	ed.			
Attach	4/a)					
Attachmen	t(s) e of References Cited (PTO-892)	4) Interview Summary	/ (PTO-413)			
	e of Relefences Cited (FTO-692) e of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail D	ate			
	mation Disclosure Statement(s) (PTO/SB/08) r No(s)/Mail Date <u>2/22/07</u> .	5) Notice of Informal F 6) Other:	Patent Application			

Application/Control Number: 10/522,036

Art Unit: 1752

DETAILED ACTION

- 1. In view of the amendment of February 8, 2007, previous 112 rejection on claims 30, 31, 39 and 40 is hereby withdrawn.
- 2. Due to newly cited prior art, the following rejections are made non-final with the Examiner's sincere apology.

Claim Rejections - 35 USC § 112

3. Claim 10 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claim 10 recites "[a] method for synthesis of the component (A) of claim 1 . . . "

That is, claim 10 is a method claim. However, claim 1, from which claim 10 depends, is a composition claim. Thus, the scope of claim 10 is indefinite. In order to overcome instant rejection, applicants need to change claim 10 to read "[t]he chemical amplification type positive photoresist composition according to claim 1, in which the component (A) is made by reacting the novolak resin with a crosslinking agent . . ."

Appropriate correction is required.

4. Claims 15-18, 21 and 22 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claims 15 and 16, applicants recite that the component (A1) comprises a unit (A1') derived from $(\alpha$ -methyl)hydroxystyrene represented by the formula (I'). Yet, in the

Art Unit: 1752

formula, R is said to be <u>H atom</u> or a methyl group: for $(\alpha$ -methyl)hydroxystyrene, R has to be a methyl group.

Appropriate correction is required.

Claim Rejections - 35 USC § 103

- 5. The text of those sections of Title 35, U.S. Code not included in this action can be found in a prior Office action.
- 6. Claims 1, 4-10, 13, 14, 30, 31, 39 and 40 are rejected under 35 U.S.C. 103(a) as being unpatentable over Bantu et al (6,072,006).

In Example 2, Bantu teaches synthesis of poly[p-(cyclohexyloxyethoxy)styrene/p-hydroxystyrene] which is prepared by reacting poly(p-hydroxystyrene) and cyclohexyl vinyl ether. In Example 4, Bantu teaches a resist composition containing the polymer of Example 2, a triphenylsulfonium salt (a photoacid generator) and a base additive. Bantu spin-coats his resist composition onto a wafer. The coated photoresist is exposed to 248 nm wavelength light, subjected to a post exposure bake and then developed. Bantu teaches (col.11, lines 59-67, col.12, lines 1-8) that the base additive is being used to *scavenge protons* present in the photoresist prior to being irradiated by the actinic radiation and that the base prevents attack and cleavage of the acid labile groups by the *undesirable acids*, thereby increasing the performance and *stability* of the resist. Since Bantu is using the base to reduce the amount of undesirable acids in the composition, it is the Examiner's position that Bantu's composition would inherently have the present range for the content of the acid component. Or, at least, the present range for the content of an acid component would have been obvious to one skilled in

Application/Control Number: 10/522,036

Art Unit: 1752

the art at the time the invention was made because it has been held that discovering an optimum value of a results effective variable involves only routine skill in the art. In re Boesch, 617 F.2d 272, 205 USPQ 215 (CCPA 1980). Bantu also teaches the equivalence of polyhydroxystyrene and novolaks as the reactant polymers (see col.4, lines 1-12). Therefore, it would have been obvious to one skilled in the art to use novolak polymer in Bantu's Example 2 as the reactant polymer with a reasonable expectation of obtaining a photoresist having high contrast, increased sensitivity and improved high temperature flow characteristics. Bantu also teaches that his polymer can additionally contain alkali insoluble monomer unit such as styrene (see col.7, lines 64-67, col.8, lines 1-6). Bantu also teaches the coating thickness to be in the range of 0.1-10 um (see col.12, lines 30-35). This range overlaps with present range of 2-7 um and thus the prior art's teaching renders obvious present range. In the case "where the [claimed] ranges overlap or lie inside ranges disclosed by the prior art," a prima facie case of obviousness would exist which may be overcome by a showing of unexpected results, In re Wertheim, 541 F.2d 257, 191 USPQ 90 (CCPA 1976). Therefore, Bantu renders obvious present inventions of claims 1, 4-10, 13, 14, 30, 31, 39 and 40.

Page 4

- 7. The Examiner would like to point out that if applicants insert the limitation of the component (B1) being a poly(bissulfonyl)diazomethane photoacid generator in claims 1, 30 and 39, the 103(a) rejection on those claims over Bantu would be overcome.
- 8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sin J. Lee whose telephone number is 571-272-1333.

Application/Control Number: 10/522,036

Art Unit: 1752

Page 5

The examiner can normally be reached on Monday-Friday from 9:00 am EST to 5:30

pm EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Cynthia Kelly, can be reached on 571-272-1526. The fax phone number for

the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for

published applications may be obtained from either Private PAIR or Public PAIR.

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Business Center (EBC) at 866-217-9197 (toll-free).

S.J.J.

S. Lee

February 28, 2007

SIN LEE

PRIMARY EXAMINED

Sin J. Len